



<b>INFORMATION DISCLOSURE STATEMENT</b>	Case Name:	M. Megens 1-10-5
	Serial No.	10/040017
	Applicant:	M. Megens, et al.
	Filing Date:	January 4, 2002
	Group:	1756


**U.S. PATENT DOCUMENTS**

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date

**FOREIGN PATENT DOCUMENTS**

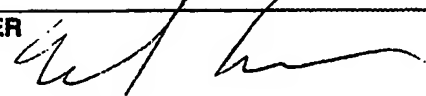
Document Number	Date	Country	Class	Subclass	Translation

**OTHER (including Author, Title, Date, Pertinent Pages, etc.)**

	AA	Lee, K.Y., LaBianca, N., Rishton, S.A., Zolghamain, S., Gelome, J.D., Shaw, J., Chang, T.H.-P., Micromachining Applications Of A High Resolution Ultrathick Photoresist, J. Vac. Sci. Technol. B 13(6) Nov/Dec 1995, pp. 3012-3016.

\*\*\*References listed beyond AZ would list as AA-1, AB-2, AC-3 thru AZ-26.

\*\*\*Note First Page ONLY Header/Footer. Subsequent pages must ONLY have page # layout as header

EXAMINER 	DATE CONSIDERED 6/29/02
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